

WEST Search History

DATE: Thursday, November 09, 2006

Hide?	<u>Set</u> <u>Name</u>	<u>Query</u>	<u>Hit</u> <u>Count</u>
	<i>DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ</i>		
<input type="checkbox"/>	L23	L22 same corrosion same (semiconductor or wafer or substrate or workpiece)	48
<input type="checkbox"/>	L22	(chamber or apparatus or reactor or vessel) same (clean\$3 or etch\$3) same (NH3 or "NH.sub.3" or ammoni\$2) same (gas or vapor or vapour)	4509
<input type="checkbox"/>	L21	l16 same corrosion same (semiconductor or wafer or substrate or workpiece)	2
<input type="checkbox"/>	L20	l16 same corrosion	11
<input type="checkbox"/>	L19	l17 same corrosion	2
<input type="checkbox"/>	L18	l16 and l5	18
<input type="checkbox"/>	L17	((chamber or apparatus or reactor or vessel) adj5 clean\$3) with (NH3 or "NH.sub.3" or ammoni\$2) with (gas or vapor or vapour)	90
<input type="checkbox"/>	L16	(chamber or apparatus or reactor or vessel) with clean\$3 with (NH3 or "NH.sub.3" or ammoni\$2) with (gas or vapor or vapour)	304
<input type="checkbox"/>	L15	L14 and ((chamber or apparatus or reactor or vessel) with (clean\$3 or etch\$3) with (HF or (hydrogen fluoride) or hydrofluoric) with (NH3 or "NH.sub.3" or ammoni\$2) with (gas or vapor or vapour))	9
<input type="checkbox"/>	L14	L13 or l12	3316
<input type="checkbox"/>	L13	(tokyo electron limited).as.	3133
<input type="checkbox"/>	L12	L11 or l10 or l9 or l8	196
<input type="checkbox"/>	L11	ogawa-jun\$.in.	127
<input type="checkbox"/>	L10	chiba-takashi\$.in.	26
<input type="checkbox"/>	L9	okada-mitsuhiro\$.in.	20
<input type="checkbox"/>	L8	hasebe-kazuhide\$.in.	46
<input type="checkbox"/>	L7	(chamber or apparatus or reactor or vessel) with(clean\$3 or etch\$3) with (HF or (hydrogen fluoride) or hydrofluoric) with (NH3 or "NH.sub.3" or ammoni\$2) with (gas or vapor or vapour)	50
<input type="checkbox"/>	L6	L5 and l4	16
<input type="checkbox"/>	L5	134/22.1,22.18,42;438/905.ccls.	4178
<input type="checkbox"/>	L4	(chamber or apparatus or reactor or vessel) same (clean\$3 or etch\$3) same (HF or (hydrogen fluoride) or hydrofluoric) same (NH3 or "NH.sub.3" or ammoni\$2) same (gas or vapor or vapour)	482
	<i>DB=EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ</i>		
<input type="checkbox"/>	L3	(chamber or apparatus or reactor or vessel) same (clean\$3 or etch\$3) same (HF or (hydrogen fluoride) or hydrofluoric) same (NH3 or "NH.sub.3" or ammoni\$2) same (gas or vapor or vapour) ((chamber or apparatus or reactor or vessel) with (clean\$3 or etch\$3)) same	31

- | | | | |
|--------------------------|----|---|----|
| <input type="checkbox"/> | L2 | ((HF or (hydrogen fluoride) or hydrofluoric) with (NH3 or "NH.sub.3" or ammoni\$2) with (gas or vapor or vapour)) | 14 |
| <input type="checkbox"/> | L1 | 08195381 | 2 |

END OF SEARCH HISTORY